

國立臺灣科技大學

學年度第

學期

Qualify Exam 考試命題用紙

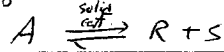
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考試科目: Advanced Chemical Reaction Engineering
(高等化工動力學)

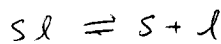
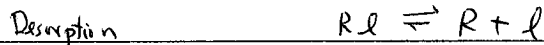
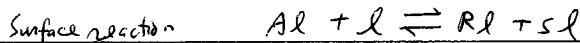
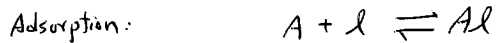
研究所
 大學部
 工程在職進修

系班別:

1. There is a solid catalyzed reaction



Following are the reaction steps for this reaction



where l represents active site. The overall rate expressions for different controlling steps are shown below:

Adsorption control:
$$-r_A = \frac{k_A (P_A - P_R P_S / K)}{1 + \frac{K_A}{K} P_A P_S + K_A P_R + K_S P_S}$$

Surface reaction control:
$$-r_A = \frac{k_{sr} K_A (P_A - P_R P_S / K)}{(1 + K_A P_A + K_R P_R + K_S P_S)^2}$$

R desorption control:
$$-r_A = \frac{k_{dr} K (P_A P_S - \frac{P_R}{K})}{1 + K_A P_A + K_R \frac{P_A}{P_S} + K_S P_S}$$

(i) If there is no R or S in the feed of reactor, please write down the rate expressions of the above controlling regimes for $t=0$, i.e. $-r_{A0}$ (initial rate expressions)

(ii) please draw schematic diagrams showing the relationships between $-r_{A0}$ and P_t for different controlling regimes. P_t is the total pressure.

2. An irreversible first-order reaction $A \rightarrow R$ takes place in a ^{spherical} porous catalyst pore surface ($R = 0.2 \text{ cm}$). If there is no film mass transfer resistance and the following data are given:

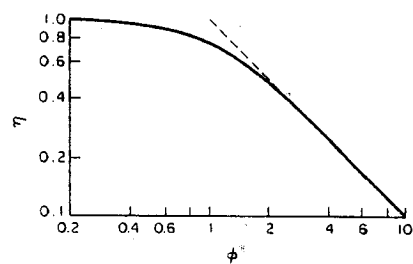
$D_e = 0.015 \text{ cm}^2/\text{s}$ at 100°C

$k_1 S_a \rho_p = 0.93 \text{ 1/s}$ at 100°C

$C_{As} = 3.25 \times 10^{-2} \text{ mol/L}$ at 100°C

$E = 20 \text{ kcal/mol}$

please calculate the value of real overall reaction rate, $-r_A$ in $\text{mol/L}\cdot\text{s}$.



Sphere $\phi = (R/3) \sqrt{k_1 S_a \rho_p / D_e}$

Cylinder $\phi = (R/2) \sqrt{k_1 S_a \rho_p / D_e}$

Slab $\phi = L \sqrt{k_1 S_a \rho_p / D_e}$

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3. A sample of the tracer *hytane* at 320k was injected as a pulse to a reactor, and the effluent concentration was measured as a function of time, resulting in the data shown in the following table.

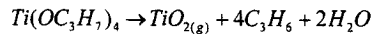
<i>t</i> (min)	0	1	2	3	4	5	6	7	8	9	10	12	14
<i>C</i> (g/m ³)	0	1	5	8	10	8	6	4	3.0	2.2	1.5	0.6	0

$$\int_0^{\infty} C(t) dt = 50 \text{ g}\cdot\text{min}/\text{m}^3$$

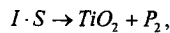
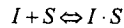
The measurements represent the exact concentrations at the times listed and not average values between the various sampling tests. Construct figures showing *C(t)* and *E(t)* as functions of time.

Undergraduate part

4. Titanium dioxide is a wide-band gap semiconductor that is showing promise as an insulating dielectric in VLSI capacitors and for use in solar cells. Thin films of TiO_2 are to be prepared by chemical vapor deposition (CVD) from gaseous titanium tetraisopropoxide (TTIP). The overall reaction is



The reaction mechanism in a CVD reactor is believed to be



where *I* is an active intermediate and P_1 is one set of reaction products (e.g., H_2O , C_3H_8) and P_2 is another set. Assuming the homogeneous gas-phase reaction for TTIP is in equilibrium, derive a rate law for the deposition of TiO_2 . The experimental results show that at 200°C the reaction is second order at low partial pressures of TTIP and zero order at high partial pressures, while at 300°C the reaction is second order in TTIP over the entire pressure range. Discuss these results in light of the rate law you derived. (20%)

5. The reaction $A \rightarrow B$ is to be carried out isothermally in a continuous-flow reactor. Calculate both the CSTR and PFR reactor volumes necessary to consume 99% of A (i.e., $C_A = 0.01 C_{A0}$) when the entering molar flow rate is 5 mol/h, assuming the reaction rate $-r_A$ is:

(a) $-r_A = k$ with $k = 0.05 \frac{\text{mol}}{\text{h}\cdot\text{dm}^3}$

(b) $-r_A = kC_A$ with $k = 0.0001 \text{ s}^{-1}$

(c) $-r_A = kC_A^2$ with $k = 3 \frac{\text{dm}^3}{\text{mol}\cdot\text{h}}$

The entering volumetric flow rate is 10 dm³/h. (15%)